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Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 246109US2		SERIAL NO. 10/725,400	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Patrice PEREZ, et al.			
				FILING DATE December 3, 2003		GROUP	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
BES	AA	5,107,221	04/21/1992	A. N'GUYEN, et al.			
	AB						
	AC						
	AD						
	AE						
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	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
	AO						
	AP						
	AQ						
	AR						
	AS						
	AT						
	AU						
	AV						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
BES	AW	F.- J. DECKER, IEEE, pages 2002-2004, XP-002260475, "CHANNELING CRYSTALS FOR POSITRON PRODUCTION", May 5, 1991					
BES	AX	M. INOUE, et al., Nuclear Instruments and Methods in Physics Research, Section - B, Beam Interactions with Materials and Atoms, vol. 173, no. 1-2, pages 104-111, XP-004223560, "EXPERIMENT OF POSITRON GENERATION USING A CRYSTAL TARGET AT THE KEK ELECTRON/POSITRON LINAC", January 2001					
BES	AY	L. V. JØRGENSEN, et al., Materials Science Form, vol. 363-365, pages 634-636, XP-008023205, "A POSITRON ACCUMULATOR FOR ANTIHYDROGEN SYNTHESIS", 2001					
BES	AZ	R. G. GREAVES, et al., Nuclear Instruments and Methods in Physics Research, Section - B, Beam Interactions with Materials and Atoms, vol. 192, no. 1-2, pages 90-96, XP-004361776, "POSITRON TRAPPING AND THE CREATION OF HIGH-QUALITY TRAP-BASED POSITRON BEAMS" May 2002				<input type="checkbox"/> Additional References sheet(s) attached	
Examiner <u>Bernard Souw</u>							
Date Considered <u>07/26/04</u>							
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							